

**OPTICAL PROXIMITY CORRECTION (OPC) TECHNIQUE USING
GENERALIZED FIGURE OF MERIT FOR PHOTOLITHOGRAPHIC
PROCESSING**

ABSTRACT OF THE DISCLOSURE

5 A method and associated computer program for making optical proximity
corrections for a reticle layout topology. Edge segments of the reticle layout
topology are manipulated to generate a corrected reticle layout accounting for
optical distortions and, based on the corrected reticle layout, a plurality of
individual figure of merit values are generated. A generalized figure of merit
10 (GFOM) using the plurality of individual figure of merit values is then generated.

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